

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 247579US2TTCRD CONT		SERIAL NO. New Application	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Yoshiaki SAITO, et al.			
				FILING DATE Herewith		GROUP Unassigned	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
HN	AA	6,430,085	8-6-2002	N. D. RIZZO	365	173	————
HN	AB	6,556,473	4-29-2003	SAITO et al.	365	158	————
HN	AC	6,639,830	10-28-2003	C. HEIDE	365	158	————
	AD						
	AE						
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	AM						
	AN						
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO			
	AO						
	AP						
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
HN	AW	J.S. MOODERA, et al., J. Appl. Phys., vol. 79, no. 8, pages 4724-4729, "FERROMAGNETIC-INSULATOR-FERROMAGNETIC TUNNELING: SPIN-DEPENDENT TUNNELING AND LARGE MAGNETORESISTANCE IN TRILAYER JUNCTIONS (INVITED)", April 15, 1996					
HN	AX	F. MONTAIGNE, et al., Applied Physics Letters, vol. 73, no. 19, pages 2829-2831, "ENHANCED TUNNEL MAGNETORESISTANCE AT HIGH BIAS VOLTAGE IN DOUBLE-BARRIER PLANAR JUNCTIONS", November 9, 1998					
HN	AY	L.F. SCHELP, et al., Physical Review B, vol. 56, no. 10, pages R-5747-R5750, "SPIN-DEPENDENT TUNNELING WITH COULOMB BLOCKADE", September 1, 1997					
HN	AZ	Y. SAITO, et al., Jpn. J. Appl. Phys., vol. 39, no. 10B, pages L-1035-L1038, "CORRELATION BETWEEN BARRIER WIDTH, BARRIER HEIGHT, AND DC BIAS VOLTAGE DEPENDENCIES ON THE MAGNETORESISTANCE RATIO IN Ir-Mn EXCHANGE BIASED SINGLE AND DOUBLE TUNNEL JUNCTIONS", October 15, 2000				<input type="checkbox"/> Additional References sheet(s) attached	
Examiner HIEN NGUYEN							
Date Considered 6/25/04							
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							